�IEEE 2016 IEEE INTERNATIONAL RELIABILITY PHYSICS SYMPOSIUM April 17th-21st 2016, Pasadena Convention Center, Pasadena, CA USA

IRPS is the preeminent conference for timely research on Reliability Physics of devices, materials, circuits, and products used in the electronics industry. IRPS is the venue where important reliability challenges and solutions are first discussed.

IRPS16 is soliciting increased participation in the following areas: Self-heating effects on transistors and circuits aging, Consumer Electronics, Reliability of 2D NAND Flash replacement technologies, Packaging

The IRPS technical program includes • Paper Presentations • Keynote and Invited Talks • Poster Session • Tutorials • Year-in-Review seminar • Workshops • Panel Discussions • Equipment **Demonstrations**

IRPS bestows awards for Best Paper, Outstanding Paper, Best Poster and Best Student Presentation

Circuits and Products

Circuit Reliability - Includes digital, mixed-signal, and RF applications; design for reliability

Circuit Aging Simulation - Includes compact modeling; statistical methods

Product IC Reliability – Includes burn-in: defect detection; on-chip sensors; modeling

Consumer Electronics Reliability - Includes smart phones; wearable devices; tablets; ultrabooks; health devices

Electronic System Reliability – Includes automotive, space, communications, medical, energy, and photovoltaic applications; screening techniques; system monitoring; failure root cause determination; modeling methodologies

Soft Errors – Includes neutron and alpha particle SER: multi-bit SER/SEU; mitigation techniques; simulation ESD and Latchup - Includes component and systemlevel ESD design; modeling and simulation

3D Assembly - Includes multichip modules; 3D integration with TSV; thermomechanical stress; wafer thinning effects

Packaging - Includes chip-package interaction; fatigue; power dissipation issues

Device, Process, and Materials

Transistors - Includes hot carrier phenomena; biastemperature instability; random telegraph noise; advanced transistor scaling challenges; Ge and III-V channels Gate Dielectrics - Includes TDDB modeling; reliability of novel gate dielectrics: modeling of progressive breakdown: gate dielectric reliability for III-V FETs

Beyond CMOS Devices - Includes reliability of tunnel FETs, transistors with 2D semiconductor (graphene, MoS₂), and spintronics

Compound/Opto Electronics - Includes reliability of wide bandgap (GaN, SiC) power devices, optoelectronics, and silicon photonics

Back-end Reliability - Electromigration; Joule heating; stress migration; low-k dielectric breakdown. Includes middle of the line

Process Integration – Includes new process related reliability issues; foundry reliability challenges Failure Analysis – Includes evidence of new failure mechanisms; advances in failure analysis techniques **Memory** – Includes DRAM and NVM; failure mechanisms in novel memory devices including 3D Flash and ReRAM

Abstract (Paper/Poster) Submission due October 12, 2015: Your two-page original abstract submission should clearly and concisely present specific results, and explain the importance of your work in the context of prior work. Use the IRPS document template available at www.irps.org. Notification of acceptance will be made by December 17, 2015. Full manuscripts of accepted papers will be due before the conference. Registration for the conference is required for the author presenting the paper.

Late Paper Submission: Space permitting, full-length manuscripts with late breaking news may be considered for inclusion in the conference/proceedings. Due January 11, 2016.

Technical Program

Chair: Elyse Rosenbaum (U Illinois U-C, 1-217-333-6754, elyse@illinois.edu) Vice Chair: Cathy Christiansen (IBM, 1-802-769-0565, christia@us.ibm.com)

General Chair

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